

SPECIFICATION AMENDMENTS:

Please amend paragraph [0026] as follows:

[0026] The feature of the invention resides in that the photo-reflective layer 225 within the reflective area R2 and the source 215 and the drain 220 of the thin film transistor, by means of a second metal layer, are formed simultaneously. Since the photo-reflective layer 225 is electrically connected to the drain 220, it is known by people skilled in the art that the photo-reflective layer 225 functions as a reflective pixel electrode in the applied transfective TFT-LCD panel. Also, the photo-reflective layer 225 and the drain 220 are discrete, and the photo-reflective layer 225 is electrically connected to the drain 220 by the transparent electrode 235. Compared with the conventional manufacturing process which requires a third metal layer, the manufacturing process according to the present invention does not need to have the third metal layer hence reducing the number of masks needed. Moreover, the manufacturing process according to the present invention is more simplified than that of the conventional one.